# **Curriculum Vitae**

#### Kihwan Choi

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**Born** in Korea (South), 1970

#### Education

 M.S. Electronic & Electrical Engineering, Pohang University of Science and Technology, Pohang, Korea, February 1994
 Emphasis on III-V Semiconductor Device Physics, Process and Characterization Thesis: Sulfide Treated GaAs MISFETs with Gate Insulator of Photo-CVD Grown P3N5 Film

**B.S.** Electronics Engineering, Hanyang University, Seoul, Korea, February 1992 Emphasis on Electronic Circuits, Communication, Semiconductor Device, VLSI

## **Awards and Honors**

Scholarship for Ph.D. Degree Abroad, awarded by Samsung, 1999 Graduate School Fellowship, awarded by the Graduate School, Pohang University of Science and Technology, 1993 Scholarship for Undergraduate/Graduate Students, awarded by Samsung, 1991-93

#### **Papers and Patents**

"Floating-well Charge Pump Circuits For Sub-2.0V Single Power Supply Flash Memories" VLSI Circuits, 1997. Digest of Technical Papers. ,pp 61-62, 1997 "Effects of sulfide passivation on the performance of GaAs MISFETs with photo-CVD grown P3N5 gate insulators", Jpn. J. Appl.Phys., vol.34, Part1, no.2B, pp 1176-1180, 1995 "Effects of sulfide passivation on the performance of GaAs MISFETs with photo-CVD grown P3N5 gate insulators", Int. Conf. on Solid State Devices Materials, pp 619-621, Yokohama, Japan, 1994 "Sulfide treated GaAs MISFETs with gate insulator of photo-CVD grown P3N5 film", IEEE Trans. Electron Device Lett., vol. 15 no. 7, pp 251-253, IEEE, 1994 "Characteristics of sulfide treated GaAs MISFETs with photo-CVD grown P3N5 gate insulator", Journal of the KITE, 31(9), p80-84, 1994(in Korean) "Method for Erasing Data Stored in a Nonvolatile Memory Device" Pat. No: 5940326 US, pending(JP) "Charge Pump Circuits having Floating Wells Pat. No: 5986947 US, pending(JP) "Method for Erasing Memory Cells in a Flash Memory Device" Pat. No: pending(US,JP,TW) "Non-volatile Semiconductor Memory Device and Method of Driving Word Lines" Pat. No: pending(US,GB,DE,JP,TW)

"Flash Memory Device and Verify Method" Pat. No: pending(US,JP,TW) "Non-volatile Semiconductor Memory Device" Pat. No: pending(US,JP,TW)

and about 30 Korean Patents registered or under examination

## PROFICIENCIES

C under MS/DOS & UNIX. Verilog-XL, OPUS layout ( Cadence ) VHDL ( Mentor ) HSPICE ( Meta ) SYSTEM-HILO ( Genrad ) HP4145/4155A ( Hewlett Packard ) MS-3400 Series ( MOSAID Technologies Inc. )

## **Professional Experience**

| 05/94-07/00   | Senior Engineer<br>Nonvolatile Memory Product Design<br>Memory Product & Technology Division<br>Semiconductor Business<br>Samsung Electronics Co., Ltd.  |
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| 03/92-04/94   | Research Assistant at POSTECH  |
| 09/98-<br>10/97-03/98<br>04/96-09/97<br>05/95-03/96<br>07/94-01/95<br>03/92-03/93 | <ul> <li>Design and Analysis : 32M NOR type Flash EEPROM, Samsung</li> <li>Design and Analysis : 16M NOR type Flash EEPROM, Samsung</li> <li>Design and Analysis : 8M NOR type Flash EEPROM, Samsung</li> <li>Design : 128kB EPROM, Samsung for MICOM Embedded memory</li> <li>64M NAND type Flash EEPROM Design and Test, Samsung</li> <li>; Core Architecture Design for High Speed &amp; Low-Power</li> <li>; Embedded Erase/Program Logic Design, Synthesis and Verification</li> <li>; Behavior Modeling of Functional Block with VHDL &amp; Verilog Language</li> <li>; Develop Efficient Erase &amp; Program Schemes</li> <li>; Charge Pump Circuit Design for Low-Voltage Operation <ul> <li>Published VLSI Circuits in 1997 and Adopted to all Successive flash EEPROM</li> </ul> </li> <li>; High Voltage Generator Design with Voltage &amp; Temperature Variation Immunity</li> <li>; Develop Boosting Circuit for Low Voltage Read Operation</li> <li>; Test &amp; Analysis of Erase/Program Operation of fabricated devices with MS3400</li> <li>; Analysis &amp; Optimization of Core Bias Conditions for stable Writing Operation</li> <li>; Characterization of thin oxide &amp; ONO for Devices Scaling-Down</li> <li>III-V Semiconductor Project: III-V MISFETs Technology Development</li> </ul> |
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